

CLEAN EQUIPMENT FOR REMOVING POLYMER RESIDUES ON SIDEWALLS OF METAL LINES AND METHOD THEREOF

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ABSTRACT OF THE INVENTION

10 A clean equipment for removing polymer residues on sidewalls of
metal lines and method thereof are provided. The present clean
equipment comprises a stripping solution bath, at least an organic
solvent bath, an overflow bath and a dryer. A gas bubbler and a lattice-
like cassette stage are positioned within the organic solvent bath. The
gas bubbler provides gas flow in the organic solvent bath to increase the
convection of the organic solvent. The lattice-like cassette stage is used
for supporting cassettes for carrying wafers. By way of increasing the
15 number of bubbling apertures of the gas bubbler and designing the gas
bubbler structure in a way that preventing the bubbling apertures from
being blocked by the lattice-like cassette stage, the convection
effectiveness of the organic solvent is increased. Thereby, the stripping
solution can be effectively removed with the organic solvent. Besides,
20 lengthening the drip dry time of the wafer over each bath so as to
eliminate the quantity of the stripping solution left on the wafer drawn in
the overflow bath. By the above measures, metal corrosion occurred on
the sidewalls of the metal lines formed on the wafer is significantly
reduced.